AFRL-PR-WP-TP-2007-202

A NOVEL TEMPERATURE
MEASUREMENT APPROACH FOR A
HIGH PRESSURE DIELECTRIC
BARRIER DISCHARGE USING
DIODE LASER ABSORPTION
SPECTROSCOPY (PREPRINT)



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14. ABSTRACT

A tunable diode laser absorption spectroscopic technique is used to measure both electronically excited state production efficiency and gas temperature rise in a dielectric barrier discharge in argon. The effect of voltage pulse rise time on the power deposition and electronically excited state production efficiency have been measured over a operating pressure range from 100 Torr up to 500 Torr.

15. SUBJECT TERMS

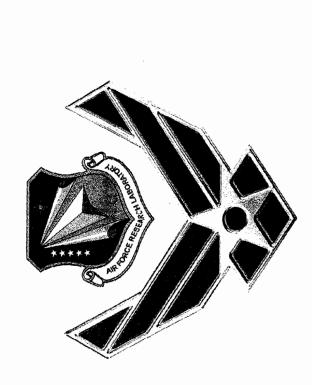
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Approach for a High Pressure DBD Using Diode Laser Spectroscopy A Novel Temperature Measurement

59th Gaseous Electronics Conference October 10-13, 2006 Columbus, Ohio



Robert John Leiweke National Research Council Washington, D.C. Biswa N. Ganguly Air Force Research Laboratory Wright-Patterson AFB, OH



Objective



To Compare the Effect of Applied Voltage Rise-Time on Argon Metastable Production Efficiency in a High Pressure, Pulse-Excitation DBD

Advantages of "Short" Pulse Excitation (dV/dt ≈10 ns)

Short pulse excitation allows "overvolting" operation to achieve a single current strike, high E/n discharge, with only a small increase in average gas temperature (e.g., Δ T< 100 Kelvin).

Disadvantages of "Short" Pulse excitation are

- External circuitry complexity and cost.
- Scaling to large electrode areas results in increased dielectric losses and increased parasitic EM effects.
- Attempting to increase power deposition by increasing the total applied voltage becomes self-limiting since the conduction current competes temporally with a comparatively larger displacement current (\propto dV/dt).¹

The objective of this study is

- Determine the extent to which high-pressure DBD operation using a degraded total applied voltage rise time can achieve high E/n operation with a single current strike as well as the subsequent effect on Ar^m production efficiency as compared to the short-pulse case.
- may be more attractive due to it's lower external circuit complexity and cost as well as the benefit of physical scalability to large area discharges. If the the long-pulse excitation production efficiency is comparable to that of the short pulse, it



Gas Parameters of Interest



1. Argon Metastable (Arm) Number Densities³

- Power deposition efficiency (e- kinetics).
- Extent to which collisional "quenching" of Arm inhibits and promotes excimer formation.

2. Average Translational Temperature 1,2

- Efficiency of power deposition into electronic states.
- E/n, governs the rate of excitation/ionization.
- High pressure operation with small temperature rise is important for Ar*₂ excimer formation and also several other applications
- In this work, pure argon is used for baseline measurements to develop tools for future studies of energy transfer kinetics involving molecular

¹ J.M. Williamson, P. Bletzinger, B.N. Ganguly, J. Phys. D: Appl. Phys. 37 (2004) 1658-1663. 30% N2/Ar DBD using TDLAS at 772.42 nm. ³J.M. Williamson, P. Bletzinger, B.N. Ganguly, J. Appl. Phys. 97 103301 (2005). 30% N2/Ar DBD using DLAS at 772.4 nm.



Optical and Electrical Diagnostics



Measurements are presented for the range 100-500 Torr:

Power deposition is used to infer the total Arm production efficiency

Quenching corrected emission at 750 nm, used for

1. A temporal bound on conduction current pulse behavior

Infer pressure scaling of excitation rates.

Average gas temperature obtained using two novel diagnostic techniques to

1. Infer the extent to which power is coupled into atomic electronic states rather than thermal heating by electron-heavy particle elastic scattering collisions.

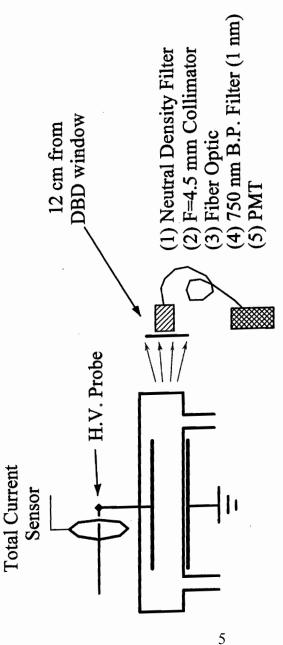
2. Estimate the PMT signal quenching correction factor.

TDLAS is used to measure both 1s, and 1s, argon metastable (Arm) populations.



Electrical and Optical Measurements







DBD Broadband Optical Emission

Current Sensor:

- •≈2 ns rise time
- 1000× H.V. Probe: ≈ 4 ns rise time, 75 MHz b.w. at -3 dB
- Used for electrical power deposition estimates

750 nm Emission:

- Quench-corrected 750 and 751 nm emission is volume averaged
- Permits estimates of the 2p₁, 2p₅ level excitation rates
- Time-integrated emission scales with peak Arm column densities



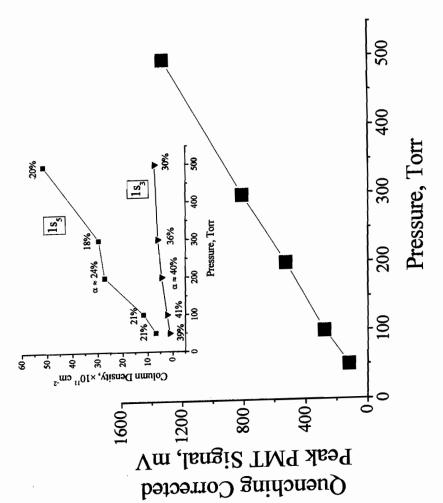
Scaling of Arm Populations with Quenching Corrected 2p_{1,5} 750 nm Emission



Previous work⁷ using <u>short-pulse excitation</u> suggested that the <u>peak</u> quench-corrected⁶ PMT signal scales with Arm column densities

⇒ Mean e energy is high enough that the e impact excitation rates are similar for both Arm and 2p₅,2p₁ levels across our pressurevoltage range

⇒ The temporal variation of the emission may be used, *in situ*, with current waveform to optimize Ar^m production efficiency as a function of pressure and total applied voltage by adjusting the breakdown time delay



7 Leiweke R.J., Ganguly, B.N., 58th Gaseous Electronics Conference, October 15-18, San Jose, CA (2005). ⁶Sadeghi N., Setser D.W., Francis A., Czarnetzki U., and Döbele H.F., J Chem Phys 115 (7), 3144 (2001).



Applied Voltage Pulse Shaping Results (300 Torr)

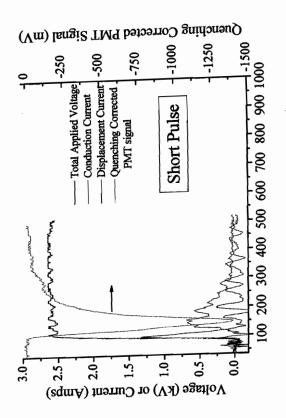


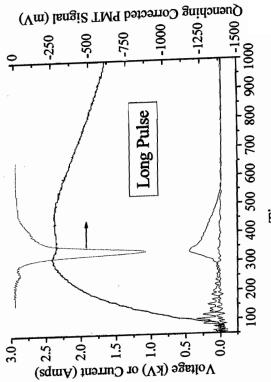
"Short Pulse": ≈10 ns Total Applied Voltage Rise Time:

- Displacement current (green) is 2x larger than the conduction current and competes temporally with conduction current (blue) with 700 mA peak.
- Peak quenching-corrected PMT signal is ≈1.5x larger than "long-pulse" case.

"Long Pulse": ≈150 ns Total Applied Voltage Rise Time

- Displacement current is smaller than the conduction current and leads by ≈100 ns.
- Quenching-corrected PMT signal and current waveforms suggest a <u>s*ingle-strike*</u> discharge.
- Discharge occurs at lower total applied voltage (2.3 kV) than the short-pulse case (2.6 kV) and the conduction current is 400 mA.







Pressure Scaling of DBD Operation



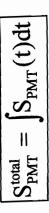
- Long-pulse pressure scaling is similar to that of the Short-pulse.
- Lower Arm production, inferred by the relative PMT signals indicates that the Long-Pulse is less efficient than the Short-Pulse.

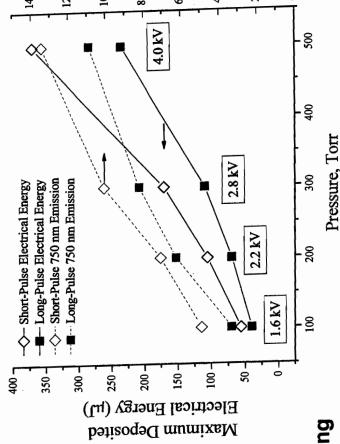
⇒These results suggest that the

Long-Pulse discharge occurs with a
single-strike but at *lower* E/n than the
Short-Pulse, but not to the extent of an
AC DBD (which exhibits multiple current
strikes at much lower E/n).

⇒Temperature and absolute Ar^m column density measurements will aid in confirming the extent of e⁻ elastic scattering (thermal heating) and Ar^m production efficiency.







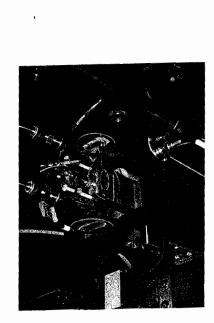
Ar 750 nm Time-Integrated (arb.unit)



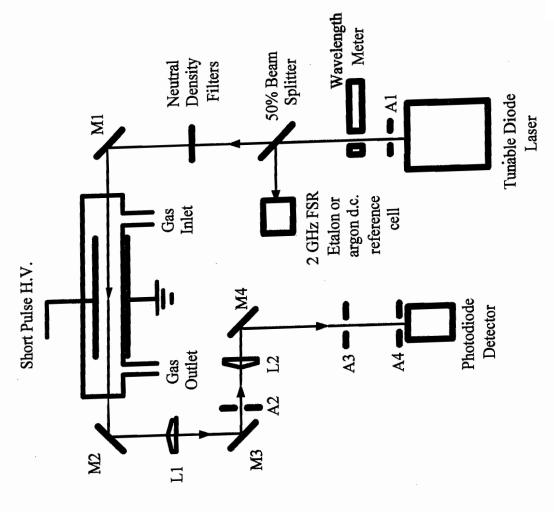
Absorption Measurement Setup

Conditions

- Argon, 25 SCCM
- Pressure = 100 500 Torr
- Unipolar, ≈200 ns FWHM total applied voltage pulses
- 5 kHz pulse repetition rate
- Applied voltage and power adjusted to maintain ≈20 % absorption of the 1s₅→2p₇ transition



Picture of DBD Layout



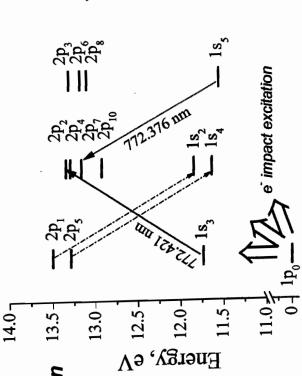


TDLAS Approach



- Arm populations can be "large" (~10¹¹ cm⁻³), even in gas mixtures with modest E/n. ^{1,2}
- Two Strong transitions ≈22.5 GHz apart³
- \Rightarrow Both 1s₃ and 1s₅ column densities can be acquired using a single, ~80 GHz scan

 $2p_2 \rightarrow 1s_3$ at 772.421 nm; A $\approx 10 \times 10^6$ s⁻¹ $2p_7 \rightarrow 1s_5$ at 772.376 nm; A $\approx 5 \times 10^6$ s⁻¹



$$\frac{B_{ls_3}}{B_{ls_5}} = \frac{A_{2p_2 - ls_3}}{A_{2p_7 - ls_5}} \frac{g_{2p_2}}{g_{2p_7}} \frac{g_{ls_5}}{g_{ls_5}}$$

$$\approx 2 \times \frac{3}{3} \times \frac{5}{1}$$

$$= 10$$

¹C. Penache, M. Miclea, A. Bräuning-Demian, et al., Plasma Sources Sci. Technol. 11 476-483 (2002). Pure argon.

 2 J.M. Williamson, P. Bletzinger, B.N. Ganguly, *J. Appl. Phys.* **97** 103301 (2005). 30% N $_2$ Ar DBD using DLAS at 772.4 nm.

³NIST Atomic Spectra Database v.3.03; http://physics.nist.gov/PhysRefData/



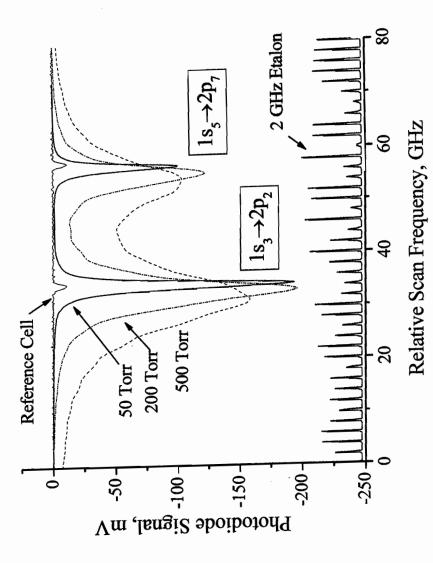
TDLAS Transmission Profiles



- ⋄ ≈80 GHz, mode-hop free tuning range using 80-200 MHz steps
- Absolute frequency shift is easily measurable above ≈100 Torr
- obtained by turning off discharge 100% transmission "baseline"
- isoenergetic, so we might expect • The 1s₃,1s₅ levels are nearly n_{1s3}=n_{1s5} with 10:1 peak absorptions since

$$\frac{B_{ls_3}}{B_{ls_5}} \approx 10$$

 \Rightarrow 1s₅ population > 1s₃ However, we observe 2:1





Column Density Estimation



Beer-Lambert absorption: $\tau(v) = e^{-n_1 L \sigma_{12}(v)}$

$$\tau(v) = e^{-n_1 L \sigma_{12}(v)}$$

absorption cross-section:

$$\sigma_{12}(v) = \frac{hv_{o,a}}{c} B_{12} \int_{-\infty}^{+\infty} \phi_s(\omega - v) \phi_a(\omega) d\omega$$

- Since the laser bandwidth is <100 MHz, source lineshape $\phi_S \approx$ delta function
- With 2-5% loss in accuracy, the absorption cross-section becomes:

$$\sigma_{12} \approx \frac{h \nu_{o,a}}{c} \, B_{12} \phi_a \left(\nu_{o,a} - \nu\right)$$

$$n_1L \approx \frac{-c \ln(1-\alpha)}{h_{v_{o,a}}B_{12}\phi_a(v_{o,a})}$$

For pressure > 50 Torr,
$$\Phi_a \left(v_{o,a} \right) \approx \frac{0.637}{w_v}$$

Absorption center frequency (GHz)

 $\varphi_a(v_{o,a}) = \text{Normalized absorber lineshape function evaluated at } v_{o,a} (\text{GHz}^{-1})$

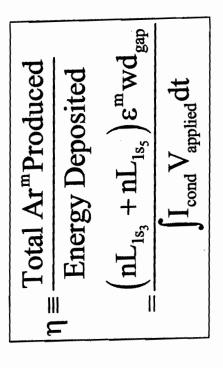
w_v = Voigt full-width at half maximum (FWHM) (GHz)

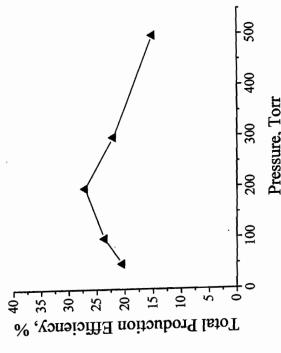


Production Efficiency Estimates



- Absorption path length = electrode width (L = 1 cm)
- Arm production assumed* to be volume-averaged and uniformly distributed within confines of the electrode geometry $(d_{gap}=0.5~cm,~w=3~cm)$
- Actual deposited energy $< \int_{cond} V_{applied}$ dt because discharge capacitance < dielectric capacitance ($V_{gap} < V_{total\ applied}$)
- Power deposition, ∫l_{cond} V_{applied} dt, assumed* to be volume-averaged over the confines of electrode geometry
- 5. Energy "cost" per metastable ϵ^m = 16 eV





*The emission and absorption measurements performed over this voltage-pressure range suggest that these assumptions are reasonably correct



Production Efficiency Estimates, cont.



• Lower Bound Arm $\eta\sim20\%$ for 50-500 Torr and given $V_{\text{total applied}}$

Peak η~27% at 200 Torr

ullet Efficiency may be increased at 500 Torr by increasing $V_{\text{total applied}}$

⇒ Breakdown time delay decreases so that the discharge operates at a higher E/n⁶



Average Gas Temperature Measurements



Based on *Lindholm-Foley theory*⁹ for van der Waals attractive potentials when no resonance occurs between the absorber & perturber:

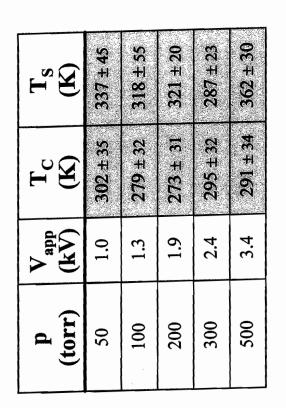
Collision Width Temperature¹⁰:
$$T_c = T_c \left| \frac{I}{V_c} \right|$$

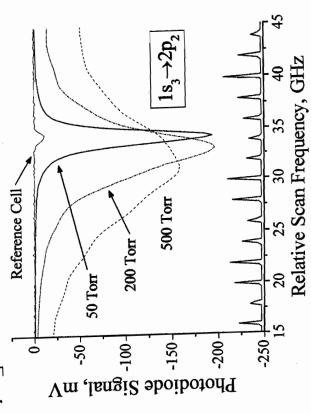
$$T_{\rm c} = T_{\rm o} \left| \frac{\Gamma_{\rm o} p}{{
m w}_{
m c}} \right|^7$$

$$\Gamma_{\rm o}$$
 (MHz/torr) = Broadening coefficient $\rm w_{\rm c}$ (MHz) = Collision width (FWHM)

Frequency Shift Temperature
10
: $T_s = T_o \left| \frac{\beta_o p}{\beta} \right|$

$$\beta_o$$
 (MHz/torr) = Freq. shift coefficient β (MHz) = Frequency shift





⁹ Breene R.G., The Shift and Shape of Spectral Lines (Pergamon, New York, 1961), pp. 47-51.

¹⁰Leiweke R.J. and Ganguly B.N., Appl. Phys. Lett. 88 131501 (2006)



Summary & Conclusions



- 750 nm quench corrected emission signal "tracks" Ar^m column densities for both "short" and "long" pulse excitation waveforms.
- Ø May be used with current waveform to optimize electron kinetics efficiency as function of pressure and total applied voltage
- Long pulse operation:
- single-strike operation is maintained
- Discharge probably operates at a lower E/n, inferred from the deposited energy and quenching corrected PMT signal in the 100-500 Torr range.
- Lower bound estimates of Arm production efficiency
- Short pulse: ~10% for 100-500 Torr
- Long pulse: ~8% for 100-500 Torr based on PMT signal scaling for Ar^m population and deposited energy
- Average gas temperature, measured using two novel techniques shows
- Short Pulse ∆T<100 K from 100-500 Torr
- Long Pulse To be determined with future TDLAS measurements
- Long pulse DBD operation may be attractive alternative to the short pulse due to lower external electrical circuitry cost, complexity, and scalability of the DBD to higher deposited power and physical scalability to larger surface area discharges.